Oxygen Reduction Reaction on Electrodeposited Pt_{100-x}Ni_x:

Influence of Alloy Composition and Dealloying

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Supporting information:

Table S1. Film thickness measured before and after dealloying for films prepared at various deposition potentials.

deposition potential V SCE	deposition Charge C/cm ²	film thickness nm	
		as-deposited (<i>d_A</i>)	dealloyed (<i>d_D</i>)
-0.100	1.13	446.4 ± 49.3	387.5 ± 7.2
-0.150	1.15	474.6 ± 26.2	409.3 ± 6.8
-0.200	1.12	417.1 ± 16.6	399.4 ± 1.4
-0.250	0.94	449.3 ± 23.1	453.4 ± 0.5
-0.300	0.98	445.0 ± 21.0	442.8 ± 1.4
-0.350	1.06	431.5 ± 51.6	425.3 ± 1.1
-0.400	1.31	510.7 ± 39.4	472.7 ± 4.1
-0.450	1.79	544.1 ± 39.8	504.4 ± 12.7
-0.500	2.19	551.0 ± 61.2	542.1 ± 35.2
-0.550	1.70	459.3 ± 55.5	434.2 ± 13.6
-0.600	1.75	547.0 ± 8.43	367.5 ± 1.4
-0.650	1.69	581.4 ± 59.7	321.0 ± 2.9
-0.700	1.79	575.4 ± 7.15	275.3 ± 19.7
-0.750	1.87	724.8 ± 15.1	341.7 ± 35.0